

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S80	6	S78 and S79	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:37
L4	1986	chemical\$4 same amplified same positive same resist	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:37
L3	836	L1 same L2	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:37
L2	833469	photoresist or resist or photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:37
L1	88432	formic adj acid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/07/03 14:37
L17	27	L16 and L15	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:38
L16	833469	resist or photoresist or photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:38
L15	27	(polystyrenesulfonic adj acid) and (pattern adj formation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/07/03 14:38
L14	7	styrenesulfonic adj acid adj ester	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/07/03 14:38

## EAST Search History

L13	59	L12 same L2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/07/03 14:38
L12	5503	styrene adj sulfonic adj acid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/07/03 14:38
L11	21	irradiat\$4 same expos\$3 same light same brewster same angle	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:38
L10	248	L8 and L9	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:38
L9	6242	430/270.1.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:38
L8	2535	430/322.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:38
L7	61	L6 and develop\$4	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:38
L6	70	chemical\$4 same amplify same resist	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:38
L5	7	L3 and L4	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/07/03 14:42
L18	2	("6057083").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/07/03 14:43